

2002 JUN 24 10 11 AM
10 Rec'd PCT/PTO 24 JUN 2002

220253US-2 PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF: :
YASUTAKA ITO ET AL : ATTN: APPLICATION DIVISION
SERIAL NO: 10/069,511 :
FILED: March 4, 2002 :
FOR: CERAMIC HEATER FOR
SEMICONDUCTOR PRODUCING/
EXAMINING DEVICE

PRELIMINARY AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Prior to a first examination on the merits, please amend the above-identified
application as follows:

IN THE TITLE

Please delete the current title and insert therefor:

CERAMIC HEATER FOR SEMICONDUCTOR
MANUFACTURING/TESTING APPARATUS

IN THE CLAIMS

Please amend claims 3 and 4 to read as follows:¹

3. (Amended) The ceramic heater according to claim 1,
wherein said resistance heating element is formed to be drawn as a curve.

4. (Amended) The ceramic heater according to claim 1,
wherein said ceramic substrate is a carbide ceramic or a nitride ceramic.

Please add new claims 5-8 as follows:

5. (New) The ceramic heater according to claim 2,
wherein said resistance heating element is formed to be drawn as a curve.

6. (New) The ceramic heater according to claim 2,
wherein said ceramic substrate is a carbide ceramic or a nitride ceramic.

7. (New) The ceramic heater according to claim 3,
wherein said ceramic substrate is a carbide ceramic or a nitride ceramic.

8. (New) The ceramic heater according to claim 5,
wherein said ceramic substrate is a carbide ceramic or a nitride ceramic.

IN THE ABSTRACT

Please delete the original Abstract on page 29 in its entirety and insert therefor:

¹A marked-up of the amendments is attached hereto.

ABSTRACT

A ceramic heater for a semiconductor producing/examining device having a resistance heating element superior in adhesion to a substrate. The ceramic heater includes a ceramic substrate and a resistance heating element formed on the surface of the ceramic substrate. Further, irregularities are formed on the side face of the resistance heating element.

REMARKS

Favorable consideration of this application, as presently amended, is respectfully requested.

The present preliminary amendment is submitted to place the above-identified application in more proper format under United States practice.

By the present preliminary amendment the Title is amended to be consistent with that in the Declaration and International publication.

Claims 3 and 4 are amended to no longer recite any multiple dependencies. Further, subject matter of the canceled multiple dependencies is now set forth in new dependent claims 5-8.

A new Abstract believed to be in more proper format under United States practice is also submitted herein.

The present application is believed to be in condition for a full and thorough examination on the merits. An early and favorable consideration of the present application is hereby respectfully requested.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.



Gregory J. Maier
Attorney of Record
Registration No. 25,599
Surinder Sachar
Registration No. 34,423



22850

(703) 413-3000
Fax #: (703) 413-2220
SNS/js

I:\atty\SNS\220253US-PR.wpd

220253US-2 PCT

Marked-Up Copy Serial No: <u>10/069,511</u> Amendment Filed on: <u>6-24-02</u>

IN THE TITLE

--[CERAMIC HEATER FOR SEMICONDUCTOR PRODUCING/EXAMINING DEVICE]

CERAMIC HEATER FOR SEMICONDUCTOR

MANUFACTURING/TESTING APPARATUS

IN THE CLAIMS

3. (Amended) The ceramic heater according to claim 1 [or 2],
wherein said resistance heating element is formed to be drawn as a curve.
4. (Amended) The ceramic heater according to [any of claims 1 to 3] claim 1,
wherein said ceramic substrate is a carbide ceramic or a nitride ceramic.

Claims 5-8 (New).

IN THE ABSTRACT

(New).--